

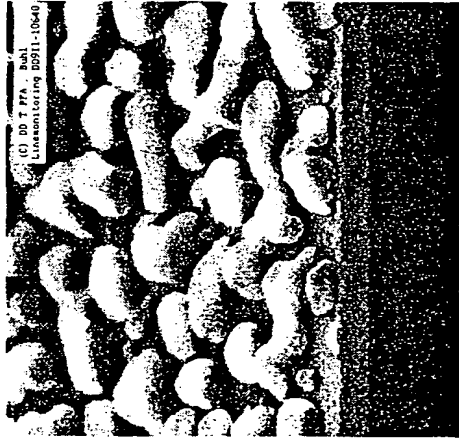
Silicon Seeding on Flat Oxide Wafers

AVP 8000

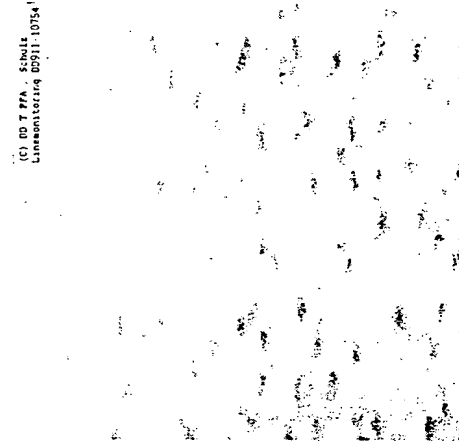


Variation of the Silane Dilution: Influence on Grain Density and Height

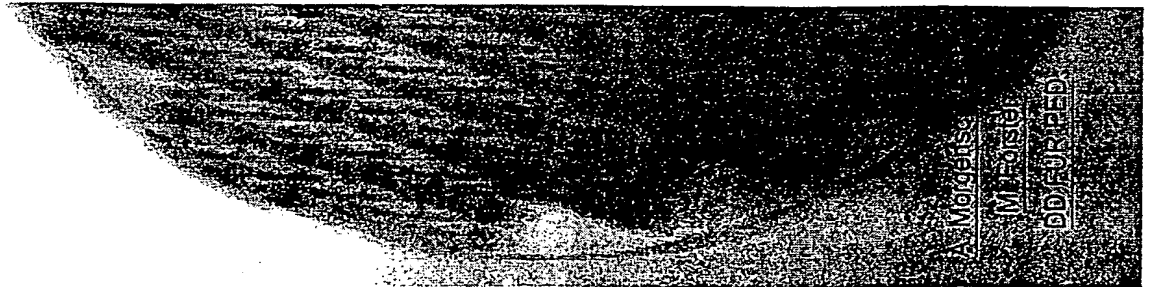
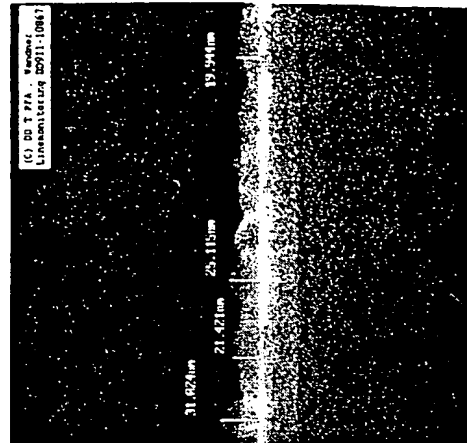
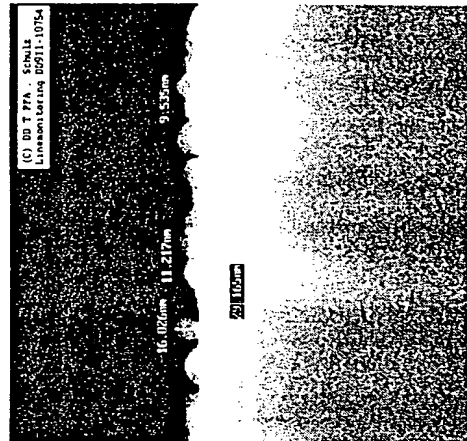
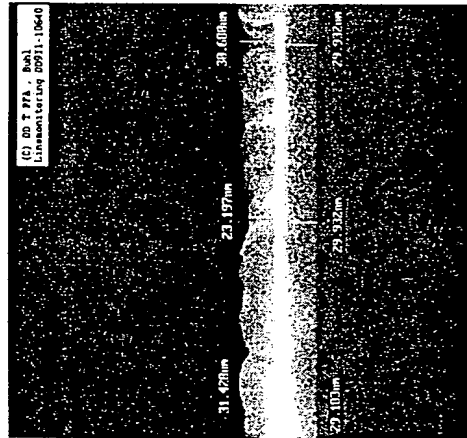
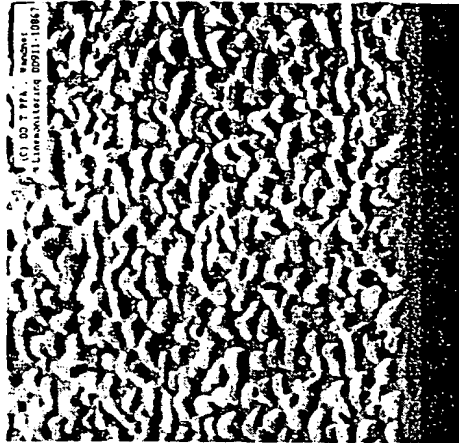
no N2 dilution / 6 min



N2 dilution 1:10 / 15 min

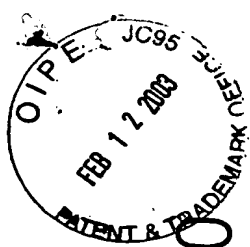


N2 dilution 1:5 / 15 min



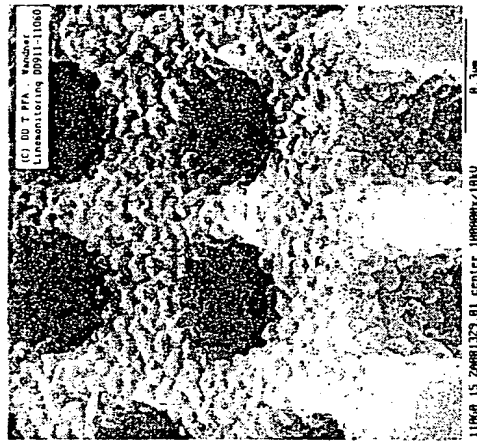
Silicon Seeding on Deep Trench Wafers

AVP 8000

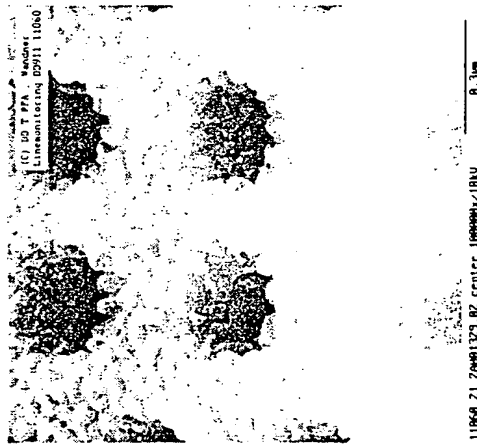


Variation of the Pre-clean: Influence on Grain Density and Height

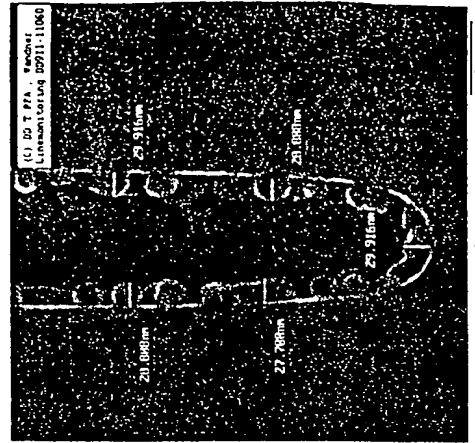
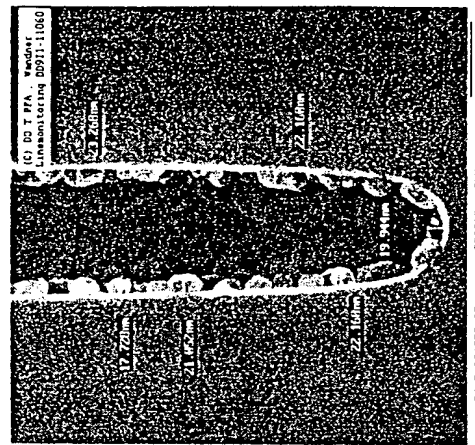
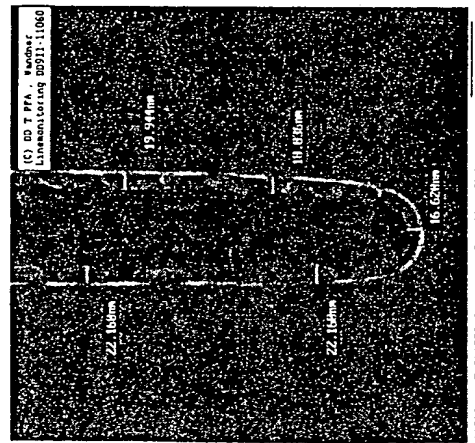
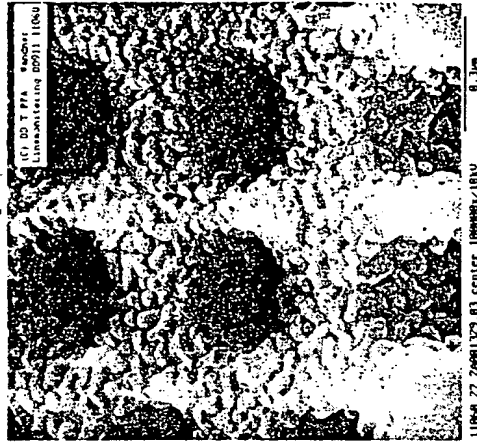
CLEAN WET PIRANHA only



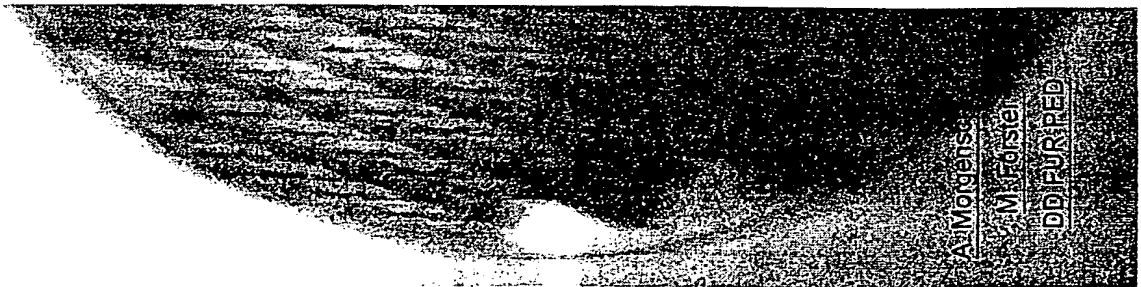
CLEAN WET DFF/HUANG/MEGASONIC



HF LAST → größere Körner



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